

AF/1746

PATENT ()

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No.

10/040,042

Confirmation No. 1835

Applicant

Wei-Yu Su

Filed

November 7, 2001

TC/A.U.

1746

Title

Method for Reduction of Photomask Defects

Docket No.

N1085-90003

Customer No.

08933

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 CERTIFICATE OF MAILING, 37 C.F.R. §1.8(a)

I certify that this correspondence and the enclosures mentioned therein are being deposited by First Class U.S. Mail with sufficient postage on the date shown below, addressed to Commissione for Patents, PO Box 1450, Alexandria, Virgina 22313–1450.

Richard A. Parkett

10/22/04

Do not enter ZE 11/8/04 ZE Sir

AMENDMENT AND RESPONSE UNDER 37 CFR §116(a)

In response to the Office Action of August 27, 2004, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.